

# WEST Search History

DATE: Wednesday, March 05, 2003

<u>Set Name</u> side by side	<u>Query</u>	<u>Hit Count</u>	<u>Set Name</u> result set
	<i>DB-USPT,PGPB,JPAB,EPAB,DWPI,TDBD; PLUR-YES; OP-ADJ</i>		
L16	L14 and target near (cu or copper)	13	L16
L15	L14 and target near (al or aluminum)	32	L15
L14	l3 and temperature	245	L14
L13	l3 and (anneal or annealed or annealing)	37	L13
L12	L11 and target near (cu or copper)	0	L12
L11	l4 and friction and target near (al or aluminum or cu or copper or ti or titanium or steel or stainless steel)	8	L11
L10	l3 and target near (al or aluminum or cu or copper or ti or titanium or co or cobalt)	64	L10
L9	l4 and friction and target near (al or aluminum or cu or copper or ti or titanium or co or cobalt)	8	L9
L8	l4 and (weld or welding) near (tig or tungsten inert)	5	L8
L7	l4 and (weld or welding) near (friction or stir)	9	L7
L6	l3 and (filler or foil or insert or intermediate or intermediary or layer or interlayer)	246	L6
L5	L4 and (weld or welding) near (e beam or electron beam or laser)	17	L5
L4	L3 and (weld or welding)	86	L4
L3	L1 and (press or pressure or pressing or pressed or force or load or hip or diffusion (bond or bonded or bonding))	294	L3
L2	L1 and (press or pressure or pressing or pressed or force or load or hip)	292	L2
L1	target and backing plate and (join or joining or bond or bonding or solder or soldering or braze or brazing or weld or welding) and (mate or mating or salient or groove or rough or grooved or roughened or interlock or interlocking or knurl or knurled or notch or notched)	329	L1

END OF SEARCH HISTORY

**WEST**☐ Generate Collection

L6: Entry 1 of 2

File: JPAB

Dec 27, 1984

PUB-NO: JP359232270A  
DOCUMENT-IDENTIFIER: JP 59232270 A  
TITLE: SPUTTERING TARGET

PUBN-DATE: December 27, 1984

## INVENTOR-INFORMATION:

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APPL-NO: JP58106460

APPL-DATE: June 14, 1983

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INT-CL (IPC): C23C 15/00; H01L 21/31

## ABSTRACT:

PURPOSE: To provide a titled target which prevents breakage and peeling from an electrode owing to thermal impact even if the power thereof is large by providing grooves having a sectional shape of a lancing type or the like for joining the electrode side of the sputtering target plate and embedding a low melting metal therein.

CONSTITUTION: Grooves 4' having a sectional shape of a lancing type are provided on the surface of a sputtering target plate 3' consisting of a metal or ceramics which contact with the cathode electrode 1' side and a low melting metal is embedded in said grooves. The target 3' thereof is adhered and fixed by indium low melting solder 2' onto the metallic cathode electrode 1'. The target constructed in the above-mentioned way has the increased mechanical joint strength between the target plate 3' and the electrode 1 and is free from crazing, peeling, etc. even if the sputtering power is large. A high deposition rate is thus obtd. The adhesive strength is further improved by constituting the section of said grooves 4' in wedge-shape or oblique with respect to the plane of the plate 3'.

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